Amendments to the Claims

1. (Currently Amended) A method for forming a flexible back plate for a display on a nonlinear roller-based system having a plurality of stations ~~composing~~ comprising the steps of:

forming an ~~idium~~ indium tin oxide (ITO) layer on a flexible substrate:

patterning the ITO layer with etch-resist material and form action protected areas to define electrode lines;

~~etch~~ etching the ITO layer in areas ~~are~~ unprotected by etch-resist material; and

forming light separating material in recesses between electrode lines.

2. (Currently Amended) A method for forming a flexible faceplate for a display on a nonlinear roller-based system having a plurality of stations ~~composing~~ comprising the steps of:

forming ~~lights~~ light separating a material ~~in~~ on a flexible substrate to define color filter lines;

forming color filter lines in areas between the light separating material, with each color ~~filters~~ filter line having a height greater than the light separating material;

forming an indium tin oxide (ITO) layer over the color ~~filters~~ filter lines and light separating material;

depositing ~~placing~~ etch-resist on the color ~~filters~~ filter lines; and

~~etch~~ etching the ITO from ~~the recessers~~ recesses between the color filter lines over the light separating material.

3. (New) A method for forming a faceplate for a display on a flexible backing on a nonlinear roller-based system having a plurality of stations, with at least one station being nonlinear, comprising the steps of:

(a) transporting the flexible backing with a first polarizing film material thereon to a first station for dispensing, defining, and curing a first filter material at a plurality of spaced locations on the first polarized film material;

(b) transporting the flexible backing with the first polarizing film material with the first filter material formed at step (a) thereon to a second station for dispensing, defining, and curing a second filter material on the first polarized film material at a plurality of locations adjacent to and spaced from the first filter material;

(c) transporting the flexible backing with the first polarizing film material with the first and second filter material formed at steps (a) and (b) thereon to a third station for dispensing, defining, and curing a third filter material on the first polarized film material at a plurality of locations adjacent to and spaced from the second and first filter material;

(d) transporting the flexible backing with the first polarizing film material with the first, second, and third filter material formed that steps (a), (b), and (c), respectively, thereon to a fourth station for depositing electrode material over the first, second, and third filter material and the first polarizing film material exposed between the first, second, and third filter material;

(e) transporting the flexible backing with the first polarizing film material with the first, second, and third filter material thereon and the electrode material deposited at step (d) to a fifth station for depositing patterned etch-resist on the electrode material over the first, second, and third filter material;

(f) transporting the flexible backing with the first polarizing film material with the first, second, and third filter material thereon and the electrode material deposited at step (d) with patterned etch-resist thereon to a sixth station for removing the electrode material from areas on which patterned etch-resist is not deposited;

(g) transporting the flexible backing with the first polarizing film material with the first, second, and third filter material that have an electrode thereon to a seventh station for depositing etch-resist on each electrode for forming alignment structures therein; and

(h) transporting the flexible backing with the first polarizing film material with the first, second, and third filter material that have an electrode thereon with patterned etch-resist for forming alignment structures therein to an eighth station for removing the electrode material from areas on which patterned etch-resist is not deposited.

4. (New) The method as recited in claim 3, wherein the first station is nonlinear.

5. (New) The method as recited in claim 3, wherein the second station is nonlinear.

6. (New) The method as recited in claim 3, wherein the third station is nonlinear.

7. (New) The method as recited in claim 3, wherein the fourth station is nonlinear.

8. (New) The method as recited in claim 3, wherein the fifth station is nonlinear.

9. (New) The method as recited in claim 3, wherein the sixth station is nonlinear.

10. (New) The method as recited in claim 3, wherein the seventh station is nonlinear.

11. (New) The method as recited in claim 3, wherein the eighth station is nonlinear.

12. (New) The method as recited in claim 3, wherein the electrode material includes indium tin oxide (ITO).

13. (New) A method for forming a back plate for a display on a flexible backing on a nonlinear roller-based system having a plurality of stations, with at least one station being nonlinear, comprising the steps of:

(a) transporting the flexible backing with a first polarizing film material thereon to a first station for depositing an electrode material on the first polarizing film material;

(b) transporting the flexible backing with the first polarizing film material with the electrode material thereon to a second station for depositing patterned etch-resist on the electrode material to define a plurality of spaced electrodes in the electrode material;

(c) transporting the flexible backing with the first polarizing film material with the electrode material that has patterned etch-resist thereon to define a plurality of spaced electrodes to a third station for removing the electrode material from areas on which the patterned etch-resist is not deposited;

(d) transporting the flexible backing with the first polarizing film material with the plurality of electrodes thereon to a fourth station for depositing etch-resist on the plurality of electrodes for forming alignment structures therein;

(e) transporting the flexible backing with the first polarizing film material with the plurality of electrodes thereon that have etch-resist for forming alignment structures therein to a fifth station for removing the electrode material from areas of the plurality of electrodes on which etch-resist is not deposited; and

(f) transporting the flexible backing with the first polarizing film material with the plurality of electrodes with alignment structure therein to a sixth station for forming spacers between the plurality of electrodes, with the spacers having a height greater than the electrodes.

14. (New) The method as recited in claim 13, wherein the first station is nonlinear.

15. (New) The method as recited in claim 13, wherein the second station is nonlinear.

16. (New) The method as recited in claim 13, wherein the third station is nonlinear.

17. (New) The method as recited in claim 13, wherein the fourth station is nonlinear.

18. (New) The method as recited in claim 13, wherein the fifth station is nonlinear.

19. (New) The method as recited in claim 13, wherein the sixth station is nonlinear.

20. (New) The method as recited in claim 13, wherein the electrode material includes indium tin oxide (ITO).